

AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

LISTING OF CLAIMS:

1. (Currently Amended) A Process process for deposition of depositing a silver film on a substrate, comprising consisting in carrying out a deposition of depositing silver by CVD on said the substrate by chemical vapor deposition of a using a silver precursor solution comprising a silver precursor and a solvent, characterized in that wherein:
 - the silver precursor is a silver carboxylate RCO_2Ag in which R is a linear or branched alkyl radical that has 3 to 7 carbon atoms, used in the form of a solution in an organic liquid;
 - the concentration of the silver precursor in the solution is between 0.01 and 0.6 mol/l;
 - the organic liquid solvent comprises an amine and/or a nitrile, and optionally a solvent compound whose evaporation temperature is less than the decomposition temperature of the silver precursor; and
 - the percentage by volume of the amine and/or the nitrile in the organic-liquid solvent is more than 0.1%.
2. (Currently Amended) The Process process according to claim 1, wherein the silver precursor is the silver pivalate $(CH_3)_3-C-CO_2Ag$.

3. (Currently Amended) The Process process according to claim 1, wherein the solvent is an organic compound that is liquid at ambient temperature and up to about 200°C under normal pressure conditions.

4. (Currently Amended) The Process process according to claim 3, wherein the solvent is selected from among the group consisting of mesitylene, cyclohexane, xylene, toluene and n-octane.

5. (Currently Amended) The Process process according to claim 1, wherein the amine is a monoamine that is selected from among the group consisting of n-hexylamine, isobutylamine, disec-butylamine, triethylamine, benzylamine, ethanolamine and diisopropylamine.

6. (Currently Amended) The Process process according to claim 1, wherein the amine is a polyamine.

7. (Currently Amended) The Process process according to claim 1, wherein the nitrile is selected from among the group consisting of acetonitrile, valeronitrile, benzonitrile and propionitrile.

8. (Currently Amended) The Process process according to claim 1, wherein the substrate is formed by a material that is selected from among the group consisting of the superconductive high T_c materials, the ceramics, the thermoresistant polymers, the glasses, MgO, LaAlO₃, Ni, Si, AsGa, InP, SiC and SiGe.

9. (Currently Amended) The Process process according to claim 1, wherein the temperature of the substrate ~~to be coated~~ on which silver is to be deposited is between 200 and 450°C.

10. (Currently Amended) The Process process according to claim 1, wherein ~~it is implemented~~ silver is deposited on the substrate under ~~in~~ an oxygen atmosphere or ~~under~~ in a hydrogen atmosphere.

11. (Currently Amended) The Process process according to claim 1, wherein silver is deposited on the substrate in the presence of a cold plasma is added around the substrate.